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ABSTRACT OF THE DISCLOSURE



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Method for Manufacturing a Surface-Treated Silicon Substrate
for Magnetic Recording Medium

Provided is a textured silicon substrate for a magnetic disk, comprising a magnetic film in which magnetic anisotropy can be attained and high recording density can be achieved, while ensuring the flying stability of a head by controlling the surface roughness of the substrate through texturing. Especially, provided is a surface-treated silicon substrate for a magnetic disk, comprising a texture formed on a surface of a silicon substrate comprising an oxide film of 0 to 2 nm thickness, and a magnetic recording medium comprising the surface-treated silicon substrate. Also provided is a method for manufacturing a surface-treated silicon substrate for a magnetic disk, comprising steps of: removing or reducing an oxide film on a surface of a silicon substrate; and forming a texture on the surface of the silicon substrate having the oxide film removed or reduced using a free abrasive-containing slurry and a tape; and a magnetic recording medium comprising the silicon substrate.

FIG. 1